

**Amendments to the Specification:**

Please replace the paragraph beginning at page 18, line 3, with the following rewritten paragraph:

--[0068] The exposure apparatus 100 may implement the illumination area detector 60, for example, by arranging a two-dimensional sensor at an incidence surface position of the optical integrator 30. However, this embodiment makes the illumination area detector 60 of the half mirror 25 and two-dimensional sensor 12. This embodiment opens the aperture stop 11, picks up an image of illumination light on the two-dimensional sensor after the half mirror 25 reflects part of the illumination light, and detects the sectional shape of the illumination light. After the shape of the illumination light is detected, an opening of the aperture stop 11 is adjusted to a desired shape, and the two-dimensional sensor 12 detects the beam shape again, compares and adjusts both shapes, and maximizes the illumination light without uselessly shielding illumination light by the aperture stop 11.--